Amendments to the Specification:

Please replace the paragraph beginning at page 20, line 1, with the following rewritten paragraph:

--An etalon 50 is shown included in the line-narrowing module of Fig. 5a. The etalon 50 is within an enclosure 52 together with the grating 35 which is attached to the heat sink 38. The pressure within the enclosure 52 is varied to tune and/or select the wavelength using over- or under-pressure, and filled with stagnant gas using no purging gas flow or flowing gas using a continuous gas flow. When no flow is used, then preferably only the port 54 is hooked up to a pump or a pressurized gas bottle is connected to it, e.g., through a pressure regulator. When continuous flow is used, then each of ports 54 and 56 is used, one as an inlet 54 and the other as an outlet 56, wherein the outlet may or may not be hooked up to a pump. Preferably, a valve or series of valves is used to control the pressure, and the pump may have variable speeds.--

Please replace the paragraph beginning at page 22, line 1, with the following rewritten paragraph:

--In the embodiment shown in Fig. 5b, the first two beam expanding prisms 30 and 31 encounter the beam as it emerges from the laser tube (not shown). Next, the beam traverses the etalon [[58]] 50 and finally the third beam expanding prism 32 prior to impinging upon the grating 35. This line-narrowing portion of the resonator may be part of a polarization coupled resonator as is known in the art (see, e.g., U.S. patents no. 5,150,370 and 5,559,816, hereby incorporated by reference).--

Please replace three paragraphs beginning at page 22, line 19, with the following three rewritten paragraphs:

--The embodiment of Fig. 5c is thus particularly preferred for lasers operating at high repetition rates (e.g., 2-4 kHz or more), and correspondingly with reduced discharge widths as described above. The third beam expanding prism 32 is disposed before the etalon [[58]] 50 in the embodiment of Fig. 5c, wherein the positions of this prism 32 and the etalon [[58]] 50 are switched from that shown and described with respect to Fig. 5b. By having the third prism 32 before the etalon [[58]] 50, the beam divergence is reduced and beam expansion is increased before the beam is incident on the etalon [[58]] 50. The reduced divergence advantageously

provides improved performance of the etalon as a smaller range of incidence angle of rays of the incident beam are subjected to the angularly dependent interference properties of the etalon.

As mentioned above, the discharge width is preferably reduced at higher rep rates to improve the clearing ratio. In the arrangement of Fig. 5b, at the larger discharge width of conventional laser systems operating at lower repetition rates, the beam has a larger geometry and preferably occupies a substantial extent of the plates of the etalon [[58]] 50. However, when the discharge width is reduced, the beam geometry is correspondingly reduced, and thus occupies a small extent of the plates of the etalon [[58]] 50. Thus, if the arrangement of Fig. 5b continues to be used, then the beam will occupy a smaller area of the plates of the etalon [[58]] 50, since the divergence and amount of beam expansion are the same and the beam began with a smaller width due to the reduced discharge width, resulting in increased localized heating.

It is desired to utilize the substantial extent of the plates of the etalon [[58]] 50. The increased beam expansion prior to the etalon [[58]] 50 provided in the embodiment of Fig. 5c allows for reduced localized heating of the etalon [[58]] 50, compared with that of Fig. 5b for a same repetition rate and discharge width. A fourth prism (not shown) may be disposed after the etalon [[58]] 50 or before the etalon [[58]] 50.--

Please replace the paragraph beginning at page 24, line 15, with the following rewritten paragraph:

--Fig. 6 schematically shows a line-narrowing module in accord with a fifth embodiment. The line-narrowing module of Fig. 6 is the same as the fourth embodiment shown in Fig. [[5]] 5a, except there is no enclosure 52 and the etalon 50 is replaced by the etalon 58. The etalon 58 differs from the etalon 50 in that the etalon 58 is preferably rotatable for tuning the wavelength output by the line-narrowing module. The etalon 50 of Fig. 5a could also be alternatively rotatable, but preferably the etalon 50 is fixed at the initially selected angle, as discussed above.--

Please replace the paragraph beginning at page 26, line 15, with the following rewritten paragraph:

--Fig. 8 schematically shows a line-narrowing module in accord with a seventh embodiment. The line-narrowing module of Fig. 8 is preferably the same as the ~~fourth~~ sixth

embodiment described with reference to Fig. 7, except there is no enclosure 61 and the etalon 60 is replaced by the etalon 68 and/or the prism 59 is replaced with the prism 66. The etalon 68 differs from the etalon 60 in that the etalon 68 is preferably rotatable for tuning the wavelength output by the line-narrowing module. Alternatively, the prism 66 may differ from the prism 59 in that the prism 66 may be rotatable or tuning the wavelength. The etalon 60 and/or prism 59 of the sixth embodiment of Fig. 7 could also be alternatively rotatable, but preferably the etalon 60 and prism 59 are fixed at the initially selected angles, as discussed above. The other prisms 30, 31 may be additionally or alternatively rotatable, and may be synchronously rotatable as set forth at the 09/244,554 application, incorporated by reference above.--